1. (Unamended From Previous Version) A structure having pores comprising:

a substrate;

a plurality of electroconductive layers formed on a surface of the substrate; a layer primarily composed of aluminum oxide covering the plurality of

electroconductive layers and the surface of the substrate where no electroconductive layer is formed; and

a plurality of pores formed in the layer primarily composed of aluminum oxide;

wherein the plurality of pores are disposed above the plurality of electroconductive layers and the surface of the substrate where no electroconductive layer is formed, with a part of the layer primarily composed of aluminum oxide provided under the plurality of pores; and

wherein the layer primarily composed of aluminum oxide provided between the bottom of the pores disposed above the electroconductive layer and the electroconductive layer comprises a material forming the electroconductive layer.

- 2. (Unamended From Previous Version) A structure having pores according to claim 1, wherein the electroconductive layer comprises at least one element selected from the group consisting of Ti, Zr, Hf, Nb, Ta, Mo, and W.
- 3. (Unamended From Previous Version) A structure having pores according to either one of claims 1 and 2, wherein the substrate comprises an insulating material.

- 4. (Unamended From Previous Version) A structure having pores according to either one of claims 1 and 2, wherein the substrate comprises an electroconductive substrate and a film composed of an insulating material provided on a surface of the electroconductive substrate.
- 5. (Unamended From Previous Version) A structure having pores according to claim 1, further comprising a material different from aluminum oxide filled in at least one of the plurality of pores.
- 6. (Unamended From Previous Version) A structure comprising pores according to claim 5, wherein the material different from aluminum oxide is filled in at least one pore disposed above the electroconductive layer.
- 7. (Unamended From Previous Version) A structure having pores according to claim 5, wherein the material filled in at least one pore disposed above the electroconductive layer is different from the material filled in at least one pore above the surface of the substrate where no electroconductive layer is formed.
- 8. (Unamended From Previous Version) A structure having pores according to claim 5, wherein the material filled in at least one pore disposed above the electroconductive layer is in electrical contact with the electroconductive layer.
- 9. (Unamended From Previous Version) A structure having pores according to any one of claims 5 to 8, wherein the material filled in at least one pore disposed above the electroconductive layer is an electroconductive material.

- 10. (Unamended From Previous Version) A structure having pores according to claim 5, wherein the material is a magnetic material.
- 11. (Unamended From Previous Version) A structure having pores according to claim 5, wherein the material has a light-emitting function.
- 12. (Aniended) A structure having pores according to Claim 46, wherein a part of the layer which is primarily composed of aluminum oxide is provided under the plurality of pores, and wherein the layer primarily composed of aluminum oxide provided between the electroconductive layer and the bottom of the pores disposed above the electroconductive layer comprises a material forming the electroconductive layer.
- 13. (Unamended From Previous Version) A structure having pores according to Claim 12, wherein the electroconductive layer comprises at least one element selected from the group consisting of Ti, Zr, Hf, Nb, Ta, Mo, and W.
- 14. (Unamended From Previous Version) A structure having pores according to either one of Claims 12 and 13, wherein the substrate comprises an insulating material.
- 15. (Unamended From Previous Version) A structure having pores according to either one of Claims 12 and 13, wherein the substrate comprises an electroconductive substrate and a film composed of an insulating material provided on a surface of the electroconductive substrate.

16. (Unamended From Previous Version) A structure having pores according to Claim 12, further comprising a material different from aluminum oxide filled in at least one of the plurality of pores.

- 17. (Unamended From Previous Version) A structure having pores according to Claim 16, wherein the material different from aluminum oxide is filled in at least one pore disposed above the electroconductive layer.
- 18. (Unamended From Previous Version) A structure having pores according to Claim 16, wherein the material filled in at least one pore disposed above the electroconductive layer is different from the material filled in at least one pore above the surface of the substrate surrounding an area at which the electroconductive layer is provided.
- 19. (Unamended From Previous Version) A structure having pores according to any one of Claims 16 to 18, wherein the material filled in at least one pore disposed above the electroconductive layer is in electrical contact with the electroconductive layer.
- 20. (Unamended From Previous Version) A structure having pores according to any one of Claims 16 to 18, wherein the material filled in at least one pore disposed above the electroconductive layer is an eletroconductive material.
- 21. (Unamended From Previous Version) A structure having pores according to claim 16, wherein the material is a magnetic material.

22. (Unamended From Previous Version) A structure having pores according to claim 16, wherein the material has a light-emitting function.

23. (Amended) An electron-emitting device comprising an electron-emitting material provided in at least one pore of a structure having pores according to claim 12.

24. (Amended) A magnetic device comprising a magnetic material provided in at least one pore of a structure having pores according to claim 12.

25. (Amended) A light-emitting device comprising a light-emitting material provided in at least one pore of a structure having pores according to claim 12.

Please add the following new claim:

46. (New) A structure having pores comprising:

a substrate;

an electroconductive layer formed on a surface of the substrate, wherein the electroconductive layer is patterned;

a layer primarily composed of aluminum oxide covering the electroconductive layer and a surface of the substrate; and

a plurality of pores formed in the layer primarily composed of aluminum oxide,

wherein the plurality of pores are disposed above the electroconductive layer and the surface of the substrate, and